

Supplementary material

Evaluation of effective mass in InGaAsN/GaAs quantum wells using transient spectroscopy

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S1. Indium and nitrogen influence on the energy band offset of InGaAsN

According to reported energy band offsets (see Galluppi, M.; Geelhaar, L.; Riechert, H.; Nitrogen and indium dependence of the band offsets in InGaAsN quantum wells. Appl. Phys. Lett. 2005 86, 131925), the linear superposition of indium and nitrogen influence was assumed to be correct in narrow concentration region. As a result, the map of the energy band offsets for conduction and valence bands was reproduced as shown in Figure S1(a) and (b).

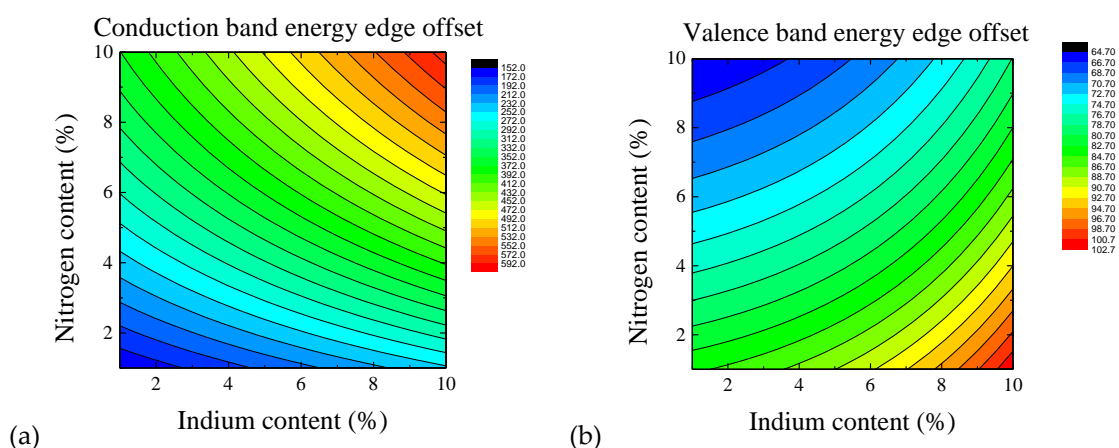


Figure S1. The energy band offsets for edges of (a) the conduction band and (b) the valence band.

S2. Quantum well thickness estimation

High-resolution x-ray diffractograms (HRXRD) were used to evaluate the quantum well thicknesses. Here follows HRXRD of investigated heterostructures.

NI49n

3 x InGaAsN/GaAs QW

In – 14,2%;

N – 0,63%

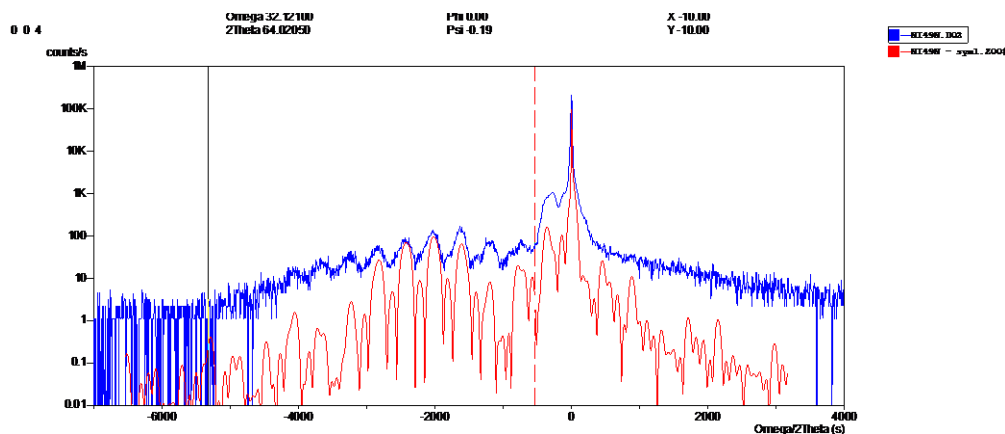
d_{QW} – 15,5 nm

d_{bariera} GaAs – 30 nm

E_{gCER} = 1,1799 eV,

E_{gBAC} = 1,1790 eV

d_{cap} – 44 nm



NI51n

3 x InGaAsN/GaAs QW

In – 14,0%;

N – 0,44%

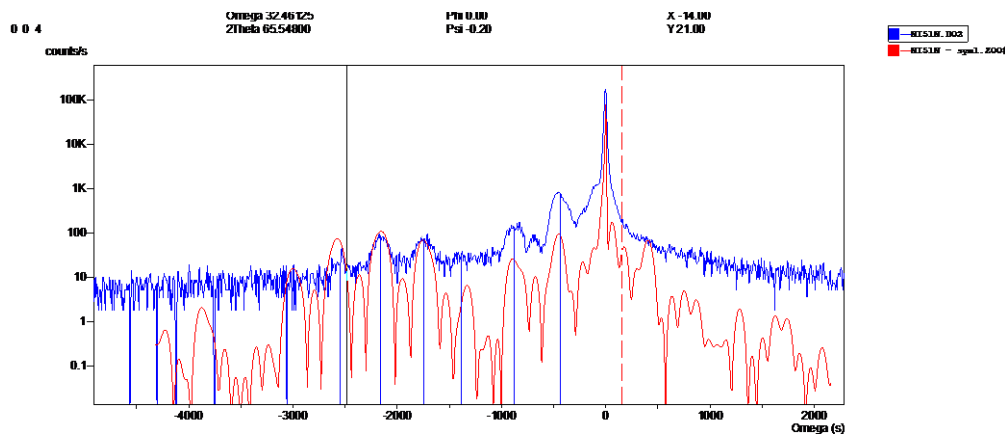
d_{QW} – 16,8 nm

d_{bariera} GaAs – 27,5 nm

E_{gCER} = 1,207 eV,

E_{gBAC} = 1,204 eV

d_{cap} – 40,0 nm



NI55n

3 x InGaAsN/GaAs QW

In – 15,2%;

N – 0,42%

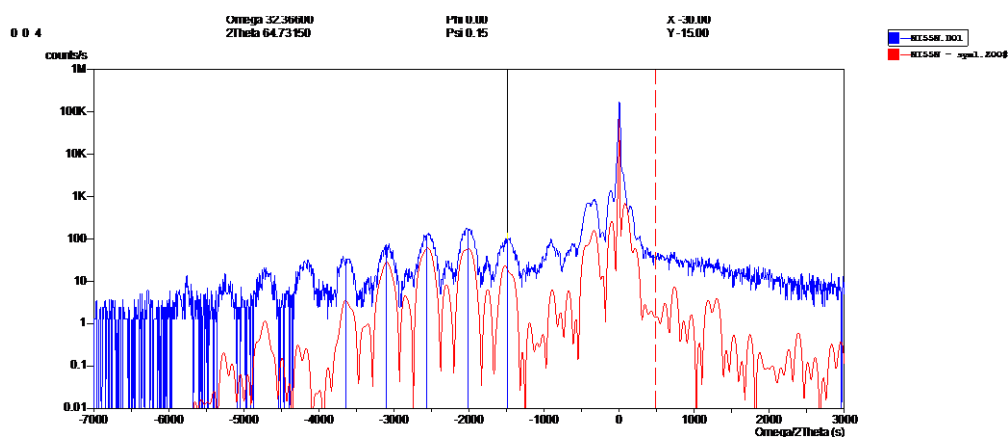
d_{QW} – 12,6 nm

d_{bariera} GaAs – 22 nm

E_{gCER} = 1,1998 eV,

E_{gBAC} = 1,200 eV

d_{cap} – 70 nm



NI57n

3 x InGaAsN/GaAs QW

In – 3,4%;

N – 0,39%

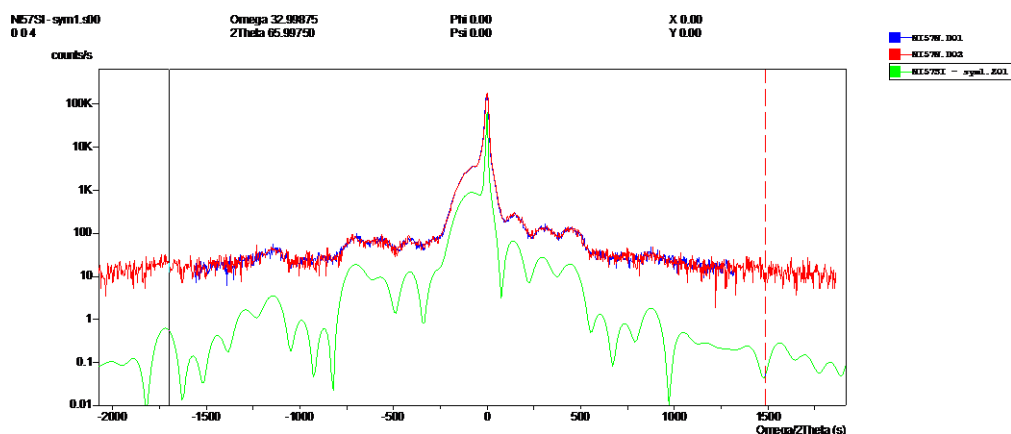
d_{QW} – 11,2 nm

$d_{\text{bariera GaAs}}$ – 24,0 nm

$E_{\text{G}_{\text{CER}}} = 1,2577 \text{ eV},$

$E_{\text{G}_{\text{BAC}}} = 1,2577$

d_{cap} – 30 nm



NI58 n

3 x InGaAsN/GaAs QW

In – 12,0%;

N – 0,41%

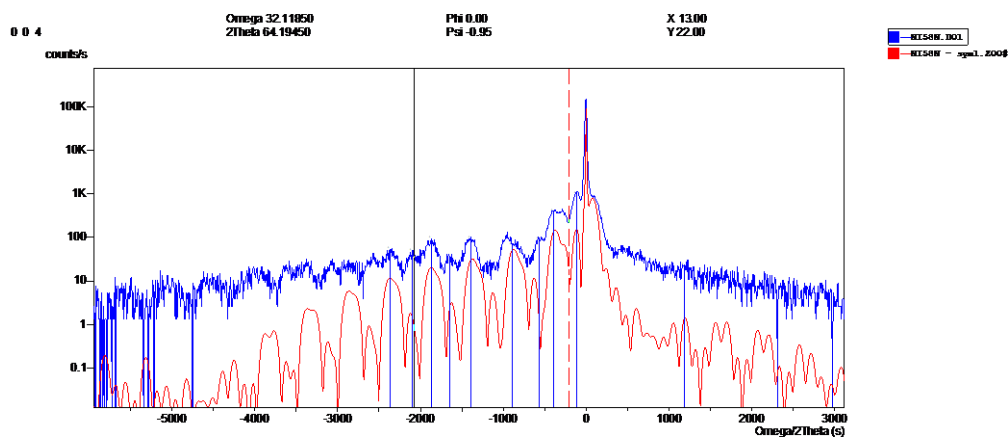
d_{QW} – 7,0 nm

$d_{\text{bariera GaAs}}$ – 31,0 nm

$E_{\text{G}_{\text{CER}}} = 1,2183 \text{ eV},$

$E_{\text{G}_{\text{BAC}}} = 1,2191 \text{ eV}$

d_{cap} – 40 nm



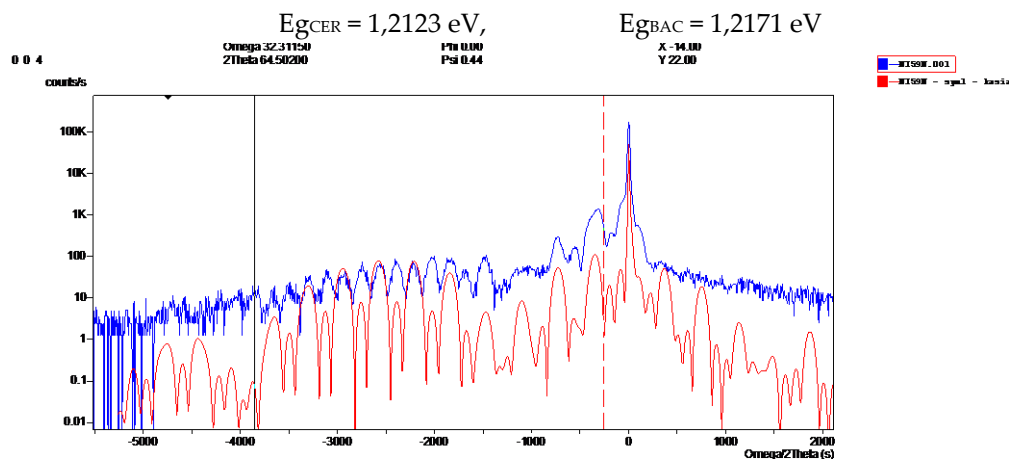
NI59n

3 x InGaAsN/GaAs QW

 $d_{\text{QW}} = 14 \text{ nm}$ $d_{\text{bariera GaAs}} = 37,0 \text{ nm}$

In – 15,5%;

N – 0,29%

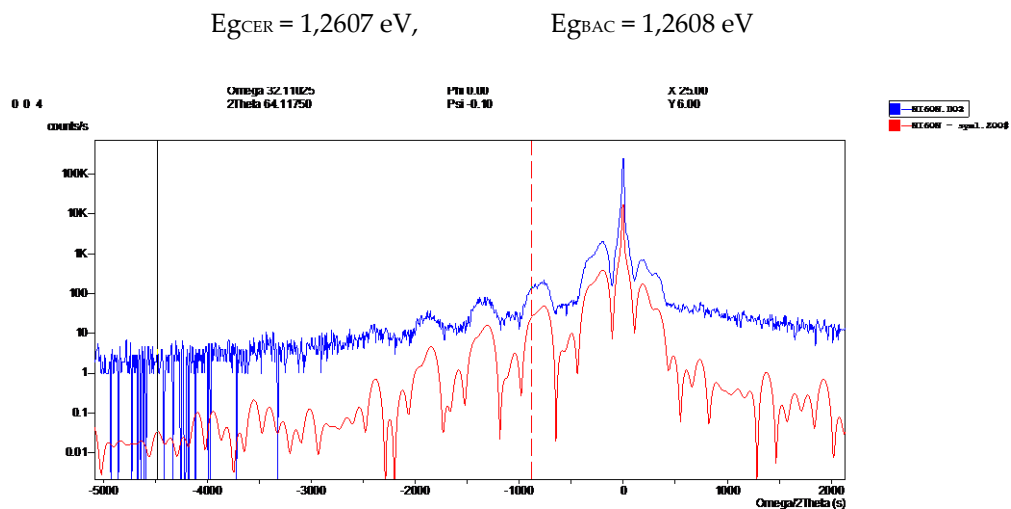
**NI60n**

3 x InGaAsN/GaAs QW

 $d_{\text{QW}} = 10,0 \text{ nm}$ $d_{\text{bariera GaAs}} = 25 \text{ nm}$ $d_{\text{cap}} = 38 \text{ nm}$

In – 6,0%;

N – 0,33%

**NI61 n**

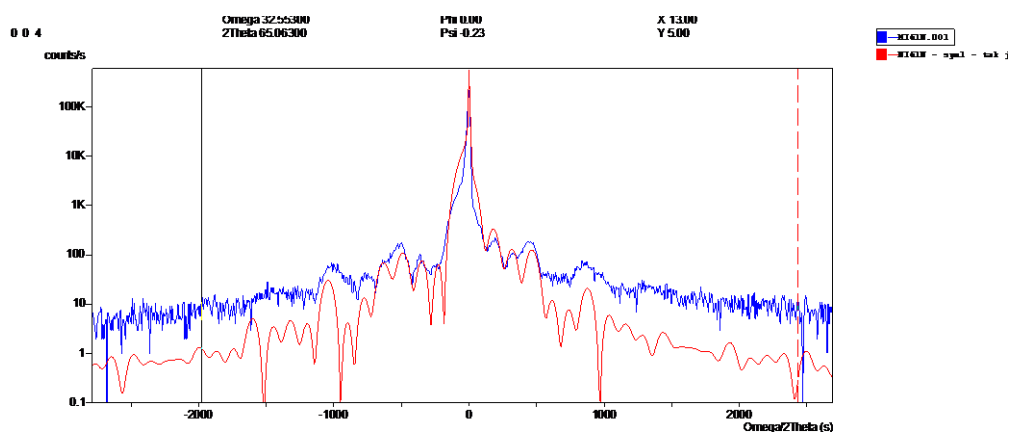
3 x InGaAsN/GaAs QW

 $d_{\text{QW}} = 10,0 \text{ nm}$ $d_{\text{bariera GaAs}} = 28 \text{ nm}$ $d_{\text{cap}} = 28 \text{ nm}$

In – 2,8%;

N – 0,45%





NI65 n

3 x InGaAsN/GaAs QW 1st layer In – 11,0% N – 0,5% d = 8,5 nm

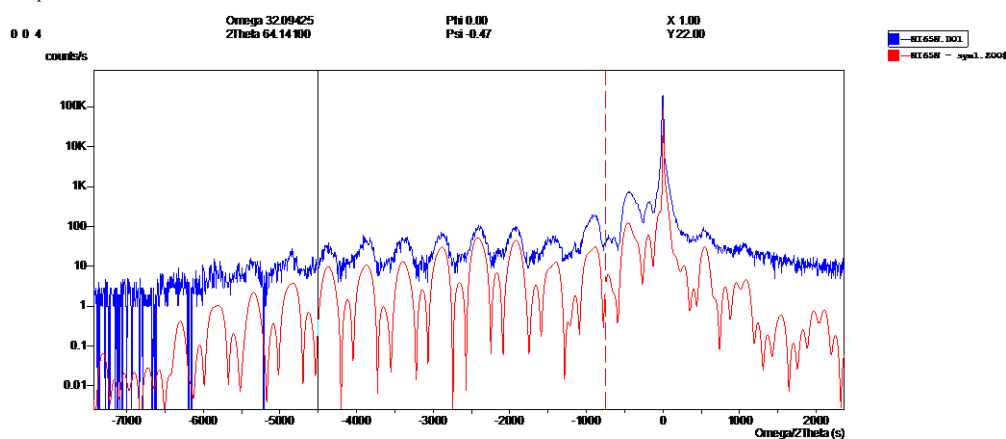
2nd layer In- 21,0% N – 0,1% d = 5,6 nm

d_{bariera} GaAs – 24,2 nm

E_GCER = 1,200 eV,

E_GBAC = 1,2029 eV

d_{cap} – 32 nm



NI66 n

3 x InGaAsN/GaAs QW

In – 15%;

N – 0,34%

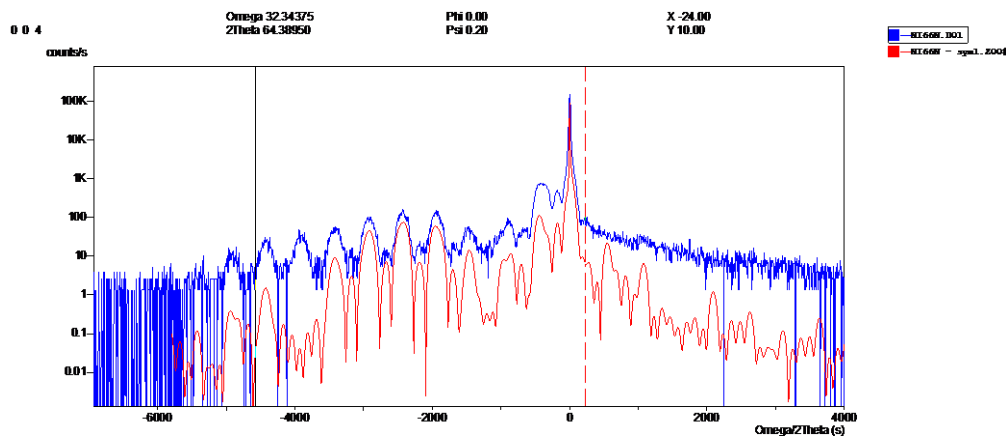
d_{QW} – 13,8 nm

d_{bariera} GaAs – 23,9 nm

E_GCER = 1,212 eV,

E_GBAC = 1,2129 eV

d_{cap} – 35,7 nm

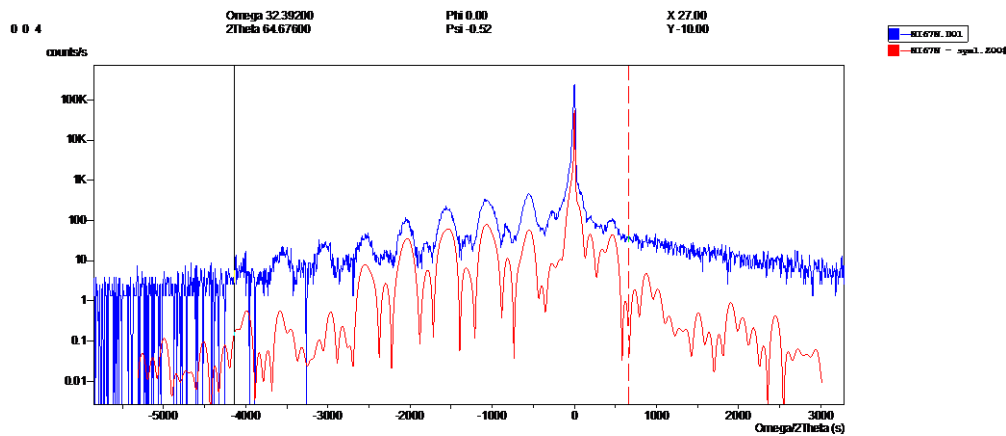


NI67 n

3 x InGaAsN/GaAs QW

In – 10,0%;

N – 0,25%

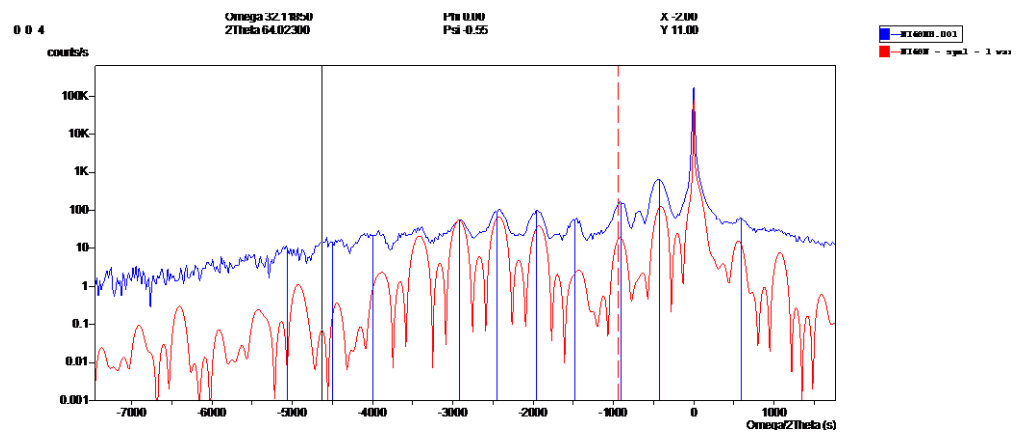
 $d_{\text{QW}} = 10 \text{ nm}$ $d_{\text{bariera GaAs}} = 25,4 \text{ nm}$ $E_{\text{gCER}} = 1,256 \text{ eV}$, $E_{\text{gBAC}} = 1,2576 \text{ eV}$ $d_{\text{cap}} = 32 \text{ nm}$ **NI68 n**

3 x

InGaAsN-

In – 16,0%;

N – 0,24%

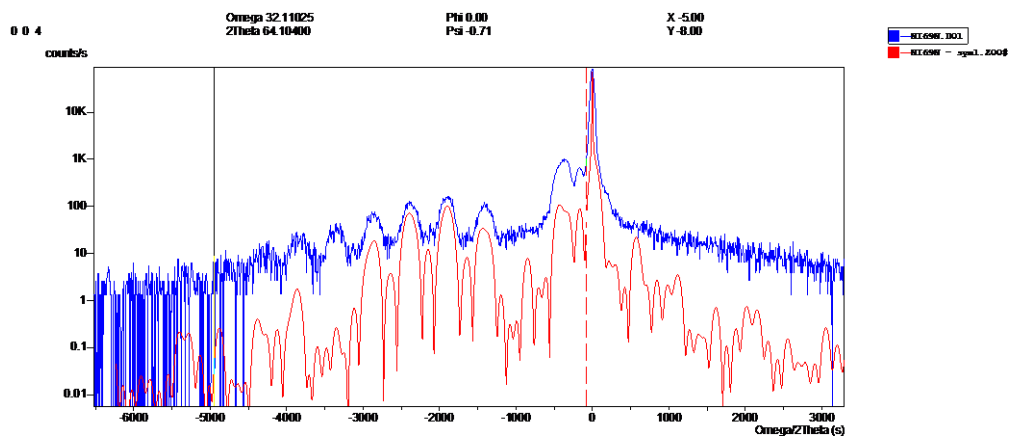
 $d = 12,5 \text{ nm}$ $d_{\text{bariera GaAs}} = 25,2 \text{ nm}$ $E_{\text{gCER}} = 1,22 \text{ eV}$, $E_{\text{gBAC}} = 1,211 \text{ eV}$ $d_{\text{cap}} = 0 \text{ nm}$ **NI69 n**

3 x InGaAsN/GaAs QW

In – 13,2%;

N – 0,36%

 $d_{\text{QW}} = 15,5 \text{ nm}$ $d_{\text{bariera GaAs}} = 22,5 \text{ nm}$ $E_{\text{gCER}} = 1,22 \text{ eV}$, $E_{\text{gBAC}} = 1,22$ $d_{\text{cap}} = 32 \text{ nm}$



NI70 n

3 x InGaAsN/GaAs QW

In – 13,3%;

N – 0,32%

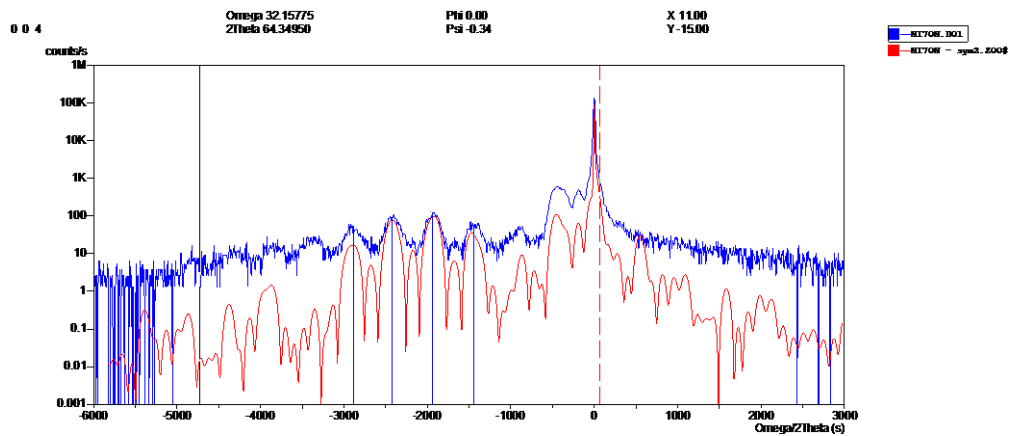
d_{QW} – 15,8 nm

d_{bariera} GaAs – 22,2 nm

E_G^{CER} = 1,225 eV,

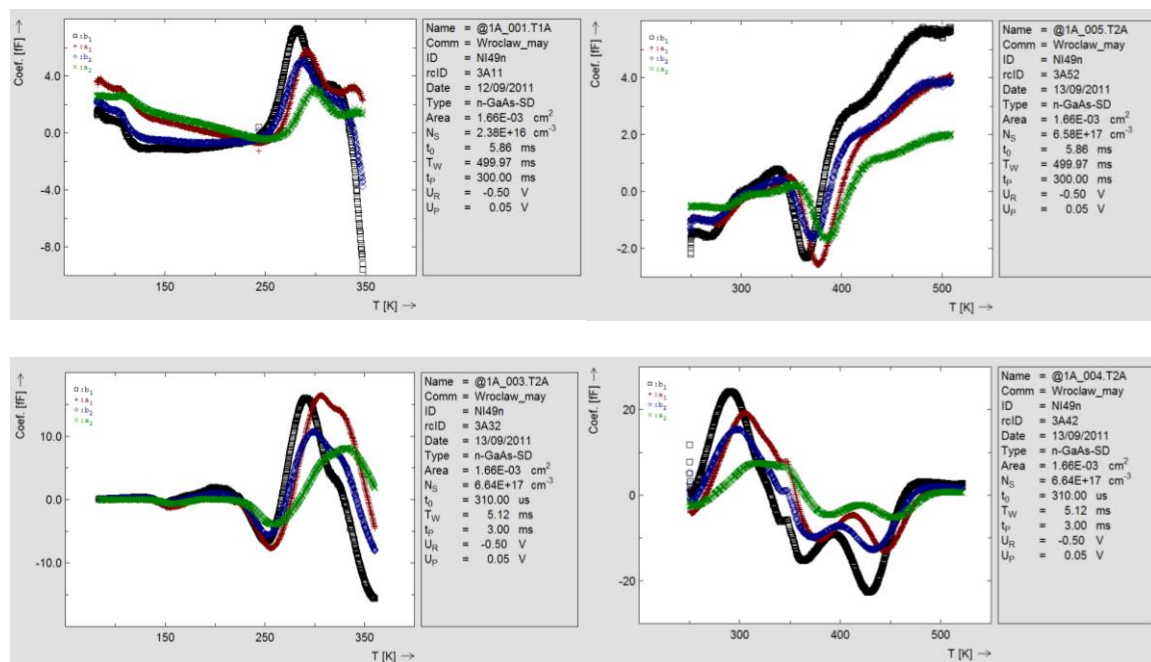
E_G^{BAC} = 1,226 eV

d_{cap} – 33 nm

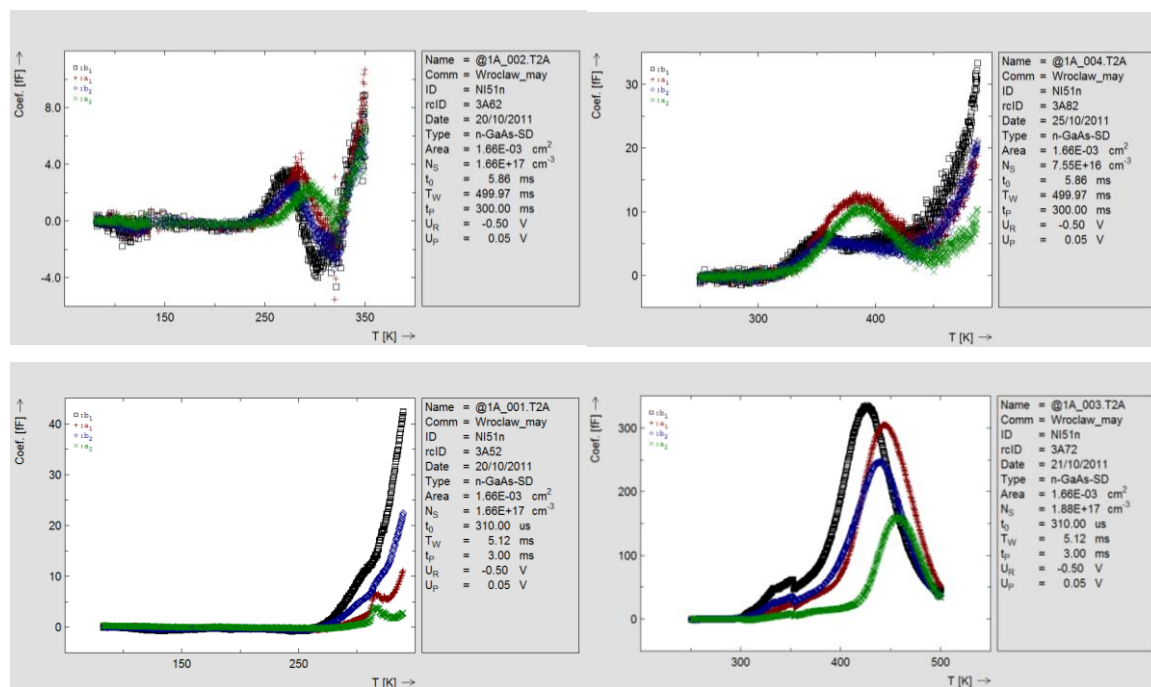


S3. Deep-level transient spectroscopy data

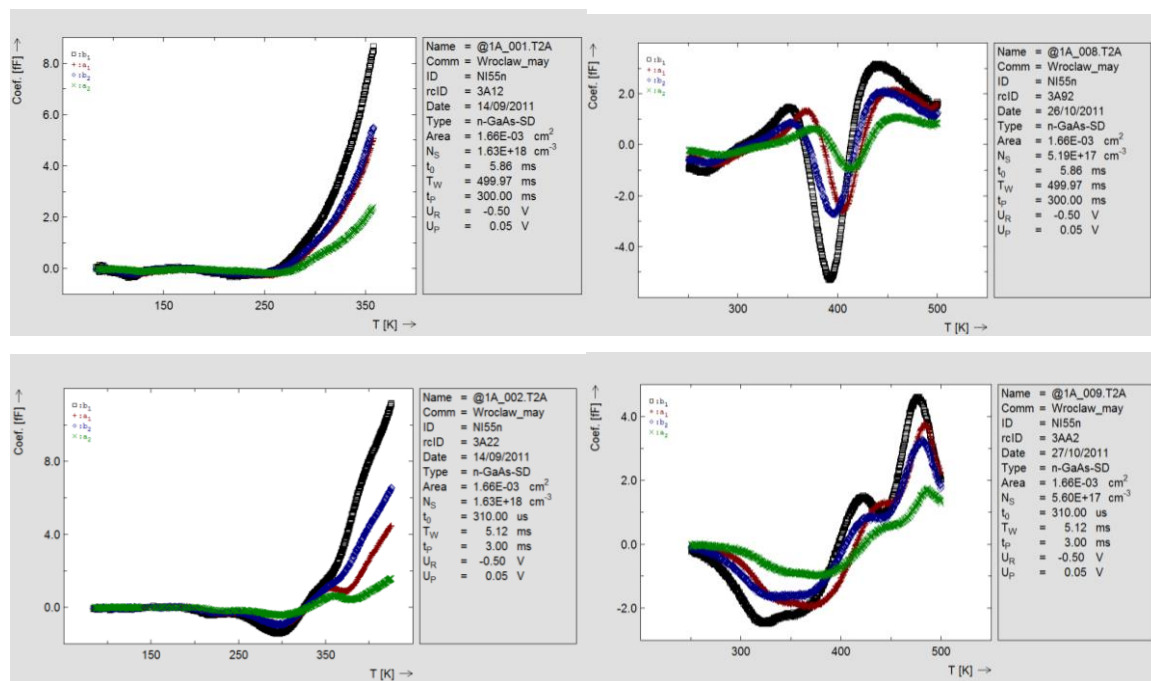
NI49n



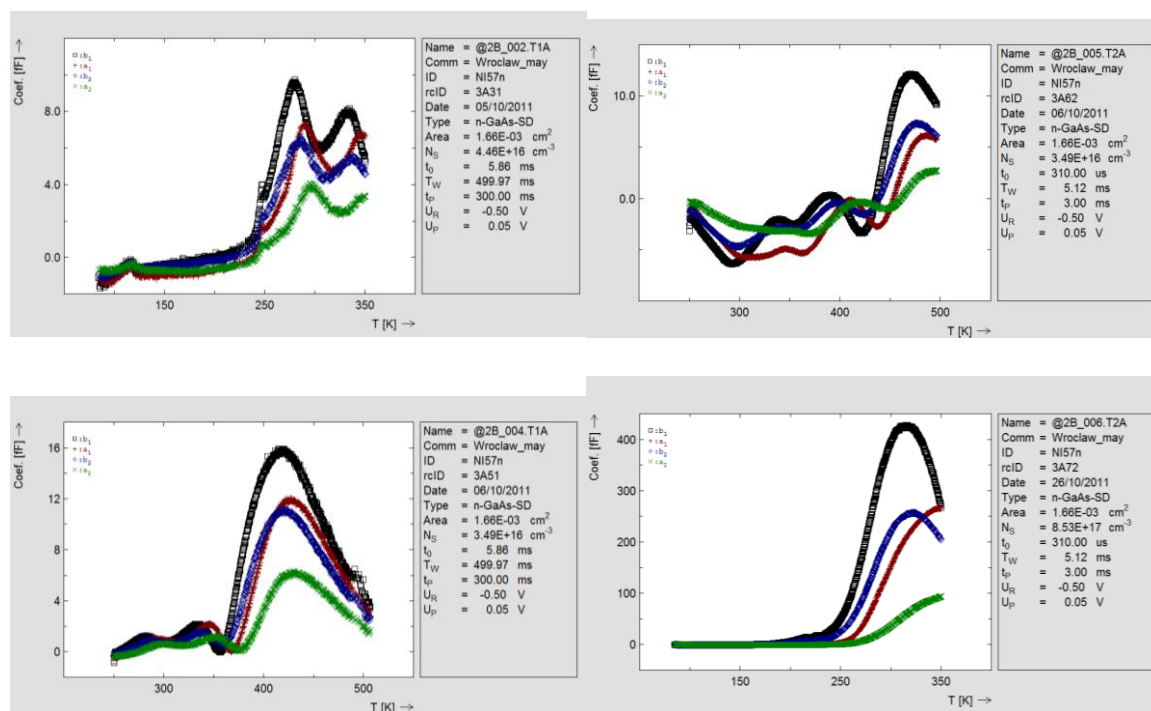
NI51n



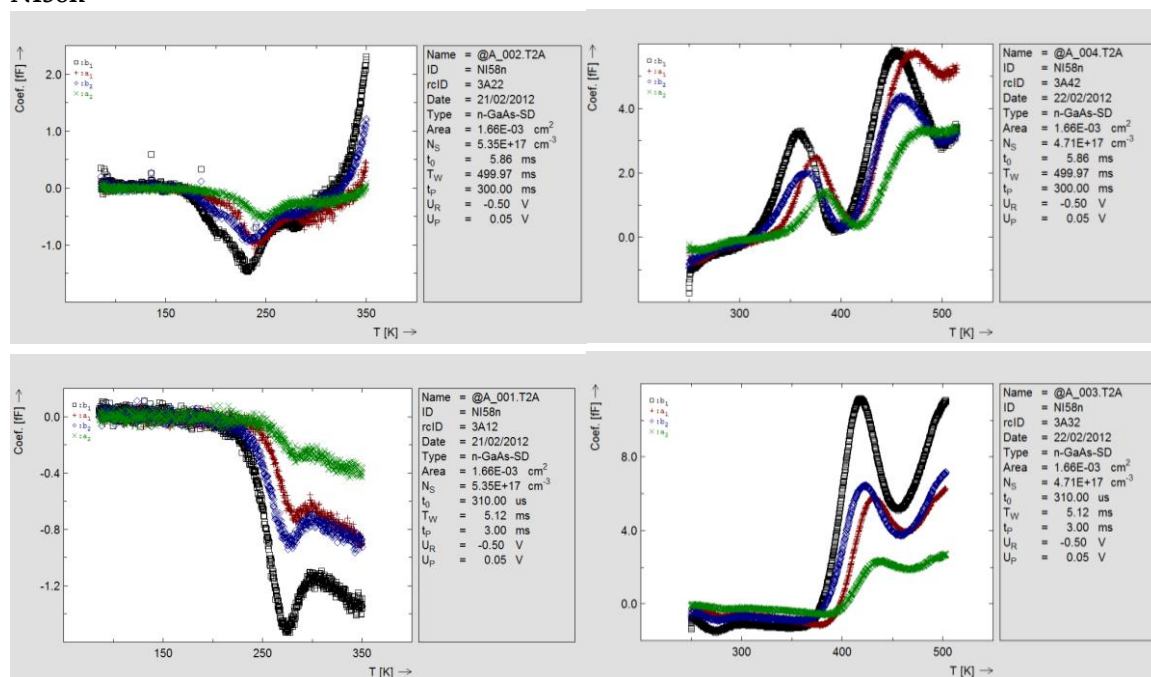
NI55n



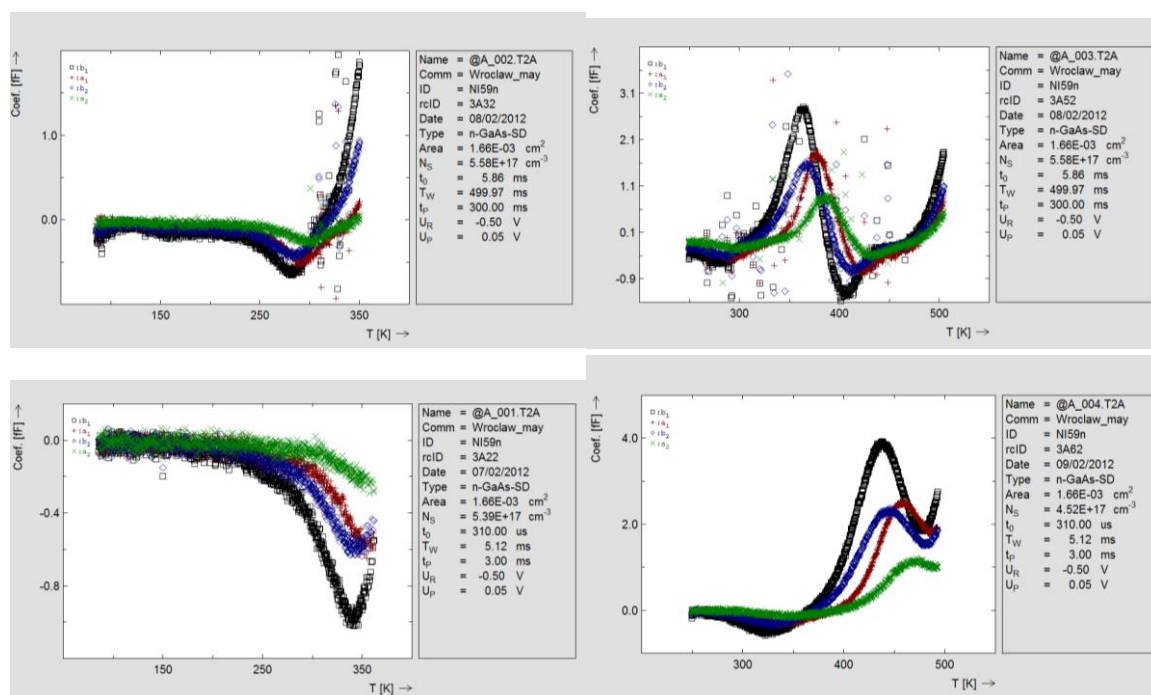
NI57n



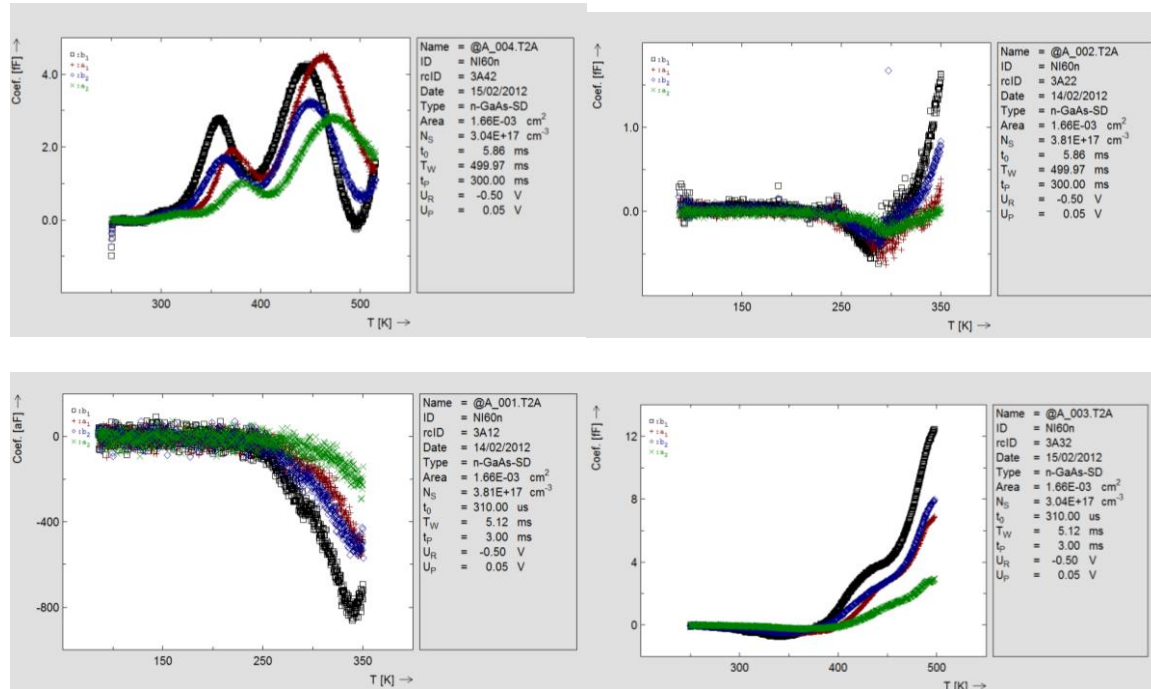
NI58n



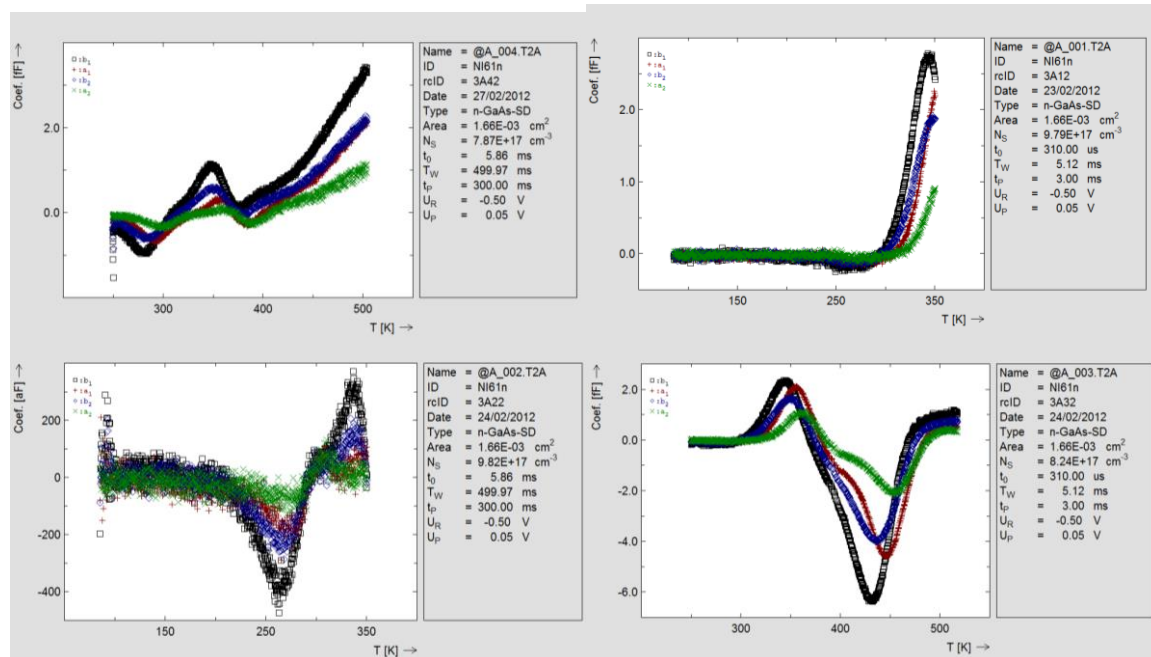
NI59n



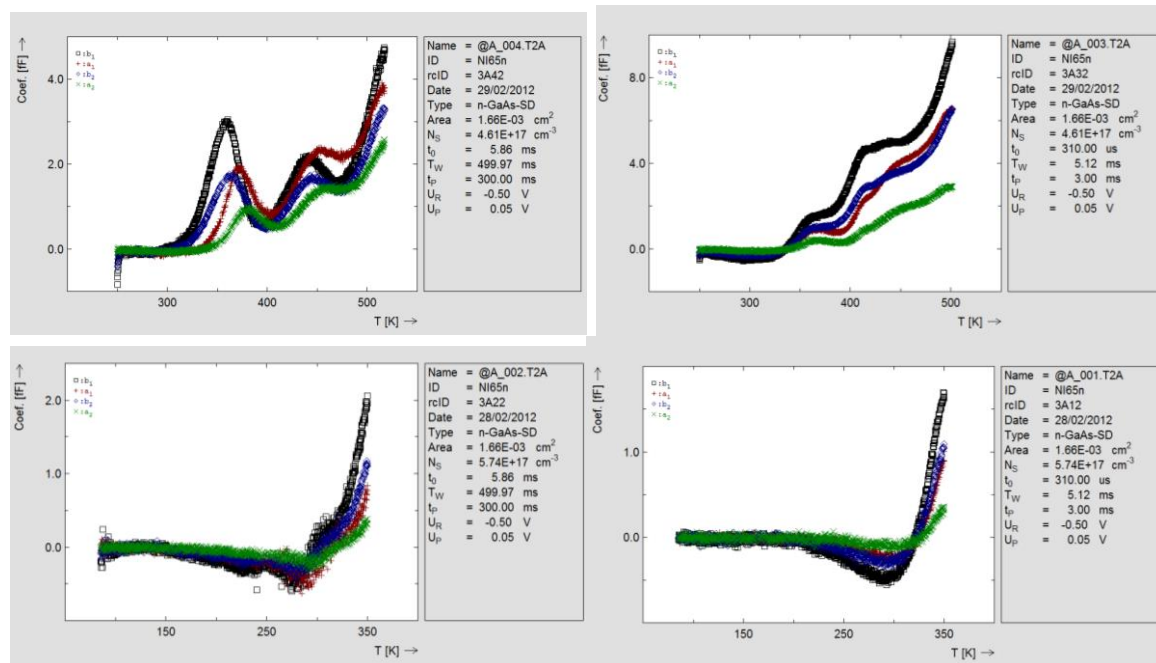
NI60n



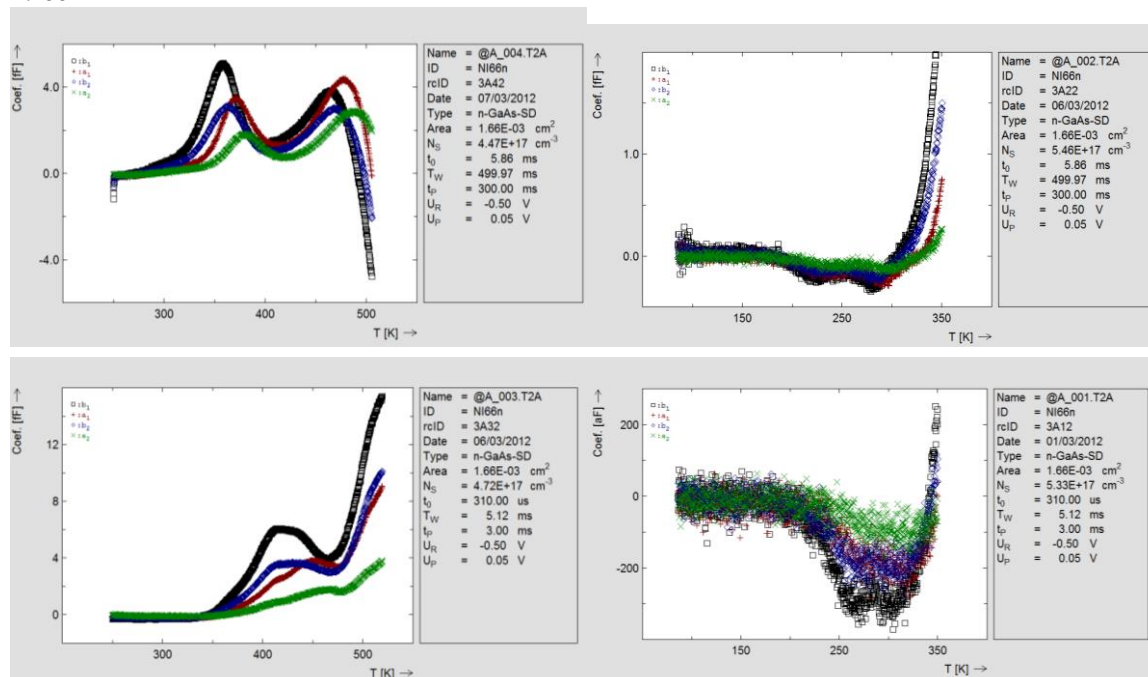
NI61n



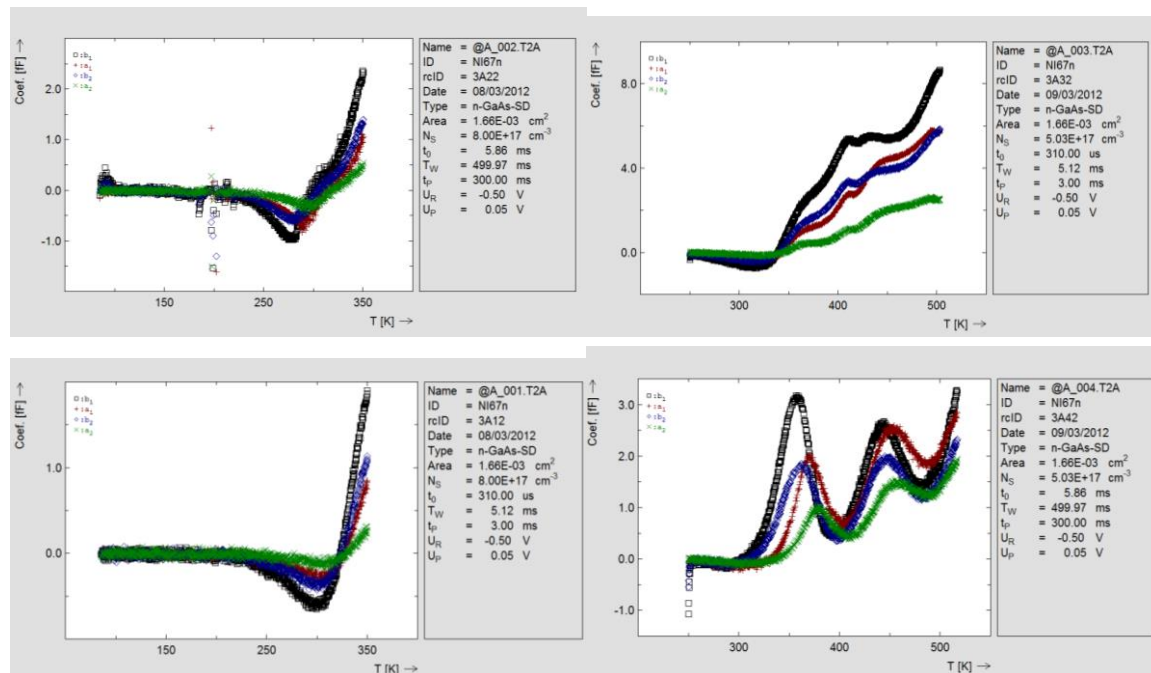
NI65n



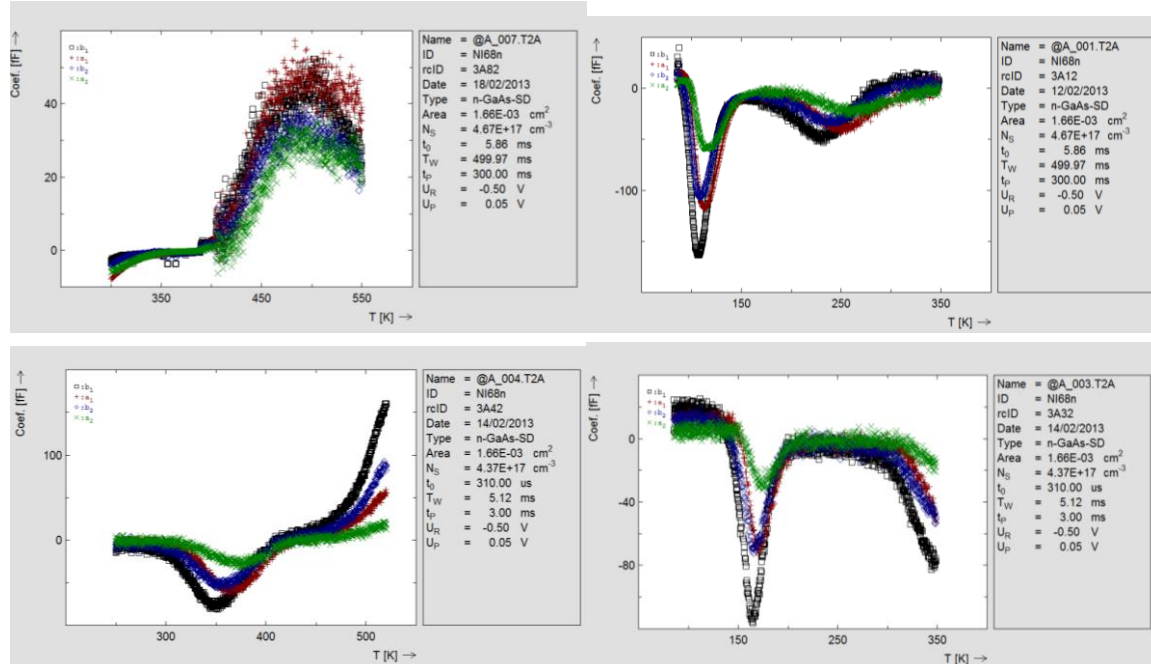
NI66n



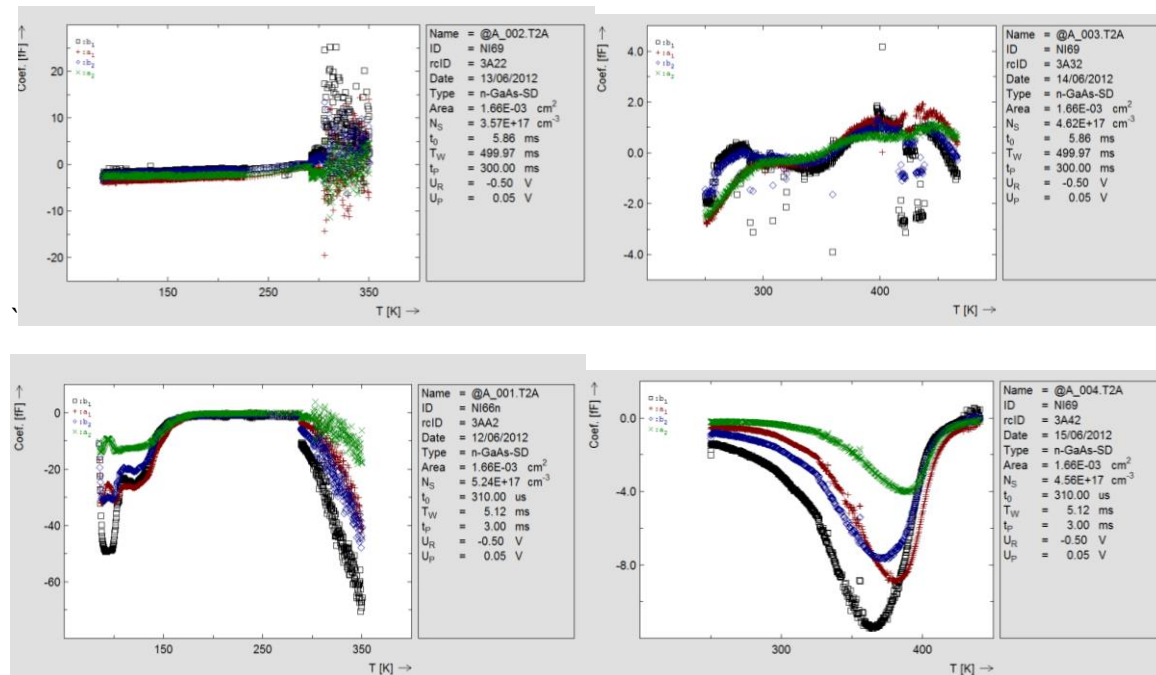
NI67n



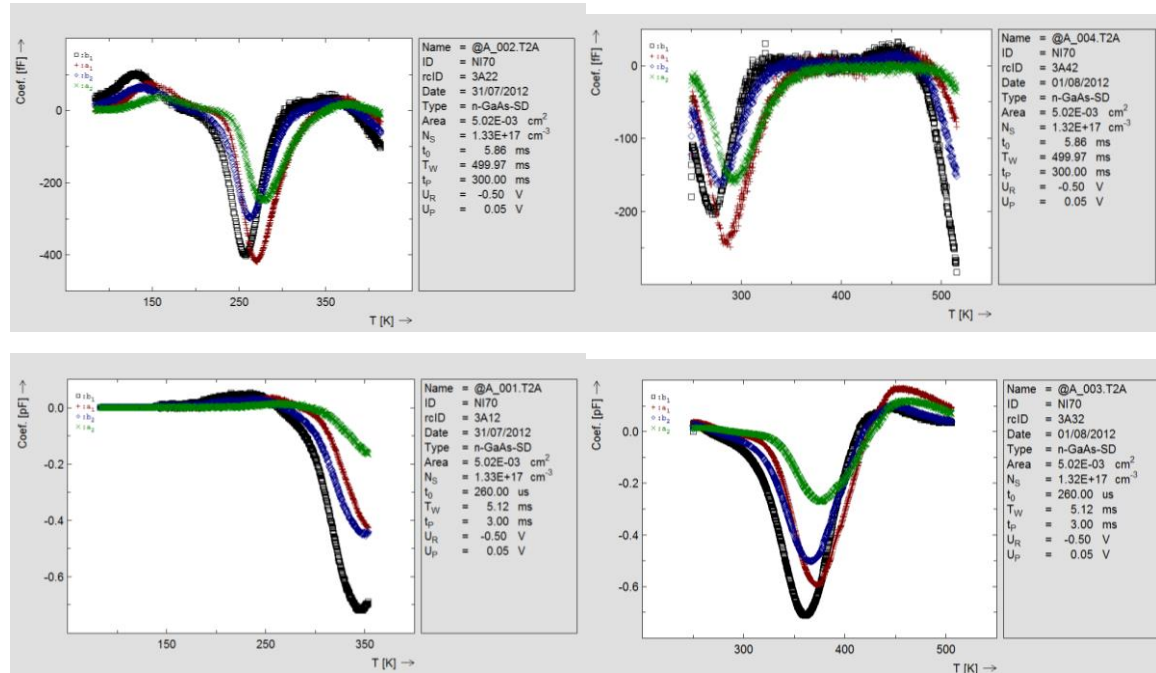
NI68n



NI69n



NI70n



I218n

